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TITLE: DEVICE FOR REMOVAL OF RESIST FILM

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INVENTOR-INFORMATION:

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ABSTRACT:

PURPOSE: To shorten a conveying time and to reduce the size of a device by providing a conveying arm having a placing unit of a substrate movable in a direction perpendicular to an shaft on the rotatable and elevationally movable shaft, and providing a treating chamber with a plurality of ozones around the shaft, and at least one cassette for containing a plurality of substrates.

CONSTITUTION: The shaft of a conveyor is rotated so that a conveying arm is directed toward the central direction of a cassette 9 on a base, the arm is elevationally moved to the position of a substrate to be removed, and the substrate is transferred to a substrate holder. The arm is rotated and elevationally moved to move the substrate to a substrate placing unit of a treating chamber for raising a chamber 18. When the substrate is placed on the unit, a chamber 17 drops, it starts rotating the unit, heating the substrate, sucking to remove gas in the chamber, and preheating and pretreating to remove organic solvent and low polymer substance from resist. A small amount of zone may be supplied at the time of pretreating, or it may be preheated while merely supplying nitrogen gas instead of sucking to remove the gas in the chamber.

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